SUPPORTING INFORMATION for

Role of Thiol Oxidation by Air in the Mechanism of

the Self-Initiated Thermal Thiol-ene Polymerization

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Thiol-ene polymerization rate. The general thiol-ene polymerization rate expression is given below (see Cramer et al. Macromolecules 2003, 36, 7964-7969 for more details)

$$R_{p} = \sqrt{\frac{R_{i}}{2k_{t}}} \times \frac{1}{\sqrt{\frac{1}{\left(k_{add}[C=C]\right)^{2}} + \frac{1}{\left(k_{H}[SH]\right)^{2}} + \frac{1}{\left(k_{add}k_{H}[C=C][SH]\right)}}}$$

R_i: initiation rate

*k*_t: rate constant for termination

 k_{H} : rate constant for H-abstraction of thiols by carbon-centered radicals

 k_{add} : rate constant for addition of thiyl radicals onto alkene

In the case of allyl ethers presented in the study, the addition rate constant is much greater than the H-abstraction rate constants ($k_{add} >> k_{H}$). For this particular case, the polymerization expression given below simplifies in a way that R_p becomes first order, and dependent only on thiol concentration (H-abstraction is the rate- limiting step).

$$R_p = \sqrt{\frac{R_i}{2k_t}} \times k_H[SH]$$



Fig. S1. Comparison between ene conversion determined by offline ¹H NMR (dots) and online FT-NIR (squares). A stoichiometric mixture (4 g) of dithiol **3** and diene **DAP** was placed in a 10 mL vial. 0.25 mL of the mixture was transferred to a quartz cuvette with an optical path 2 mm. Ene-conversion in this cuvette was monitored online using FT-NIR spectroscopy as described in detail in the main manuscript text. Aliquots were removed from the vial at different times, then placed in a NMR tube containing CDCl₃ and a ¹H NMR spectrum was recorded. In this case, ene conversion was determined by comparing the integrated resonance of the methylene protons in **DAP** at 4.75 ppm and that of the same methylene protons in the polymer at 4.25 ppm.



Fig. S2. Dependence of monomer (alkene) conversion on storage time for stoichiometric polymerization of bulk **DAA-1** performed under air. Polymerization was carried out at ambient temperature in the dark (squares) and in daylight (dots). For this latter case, the FTIR chamber was left open during the 2 hours of data acquisition (without exposure to artificial light source).



Fig. S3. Dependence of ene conversion versus time on the thiol stoichiometric polymerization of **DAA-1**. Dithiol **1** was purified after passing through an aluminum oxide column (activated, neutral, Brockmann I, 150 mesh, Sigma Aldrich Product number 199974). Briefly, 5 g of dithiol **1** was passed through a short column (12 mm ID) packed with 5 g of aluminum oxide.



Fig. S4. Effect of water on the ene conversion for the self-initiated polymerization of **3-DAP** under nitrogen (¹H NMR data); in the absence of water (squares), with added water (dots).



Fig. S5. The chemical shift of the sulfhydryl proton in thiol **1** in $CDCl_3$ was observed after adding an excess of solvent (24 equiv). A downfield shift (DMF, DMSO) corrsponds to a negative chemical shift ΔHz , while a upfield shift (CCl_4 , toluene, tert-butylbenzene) corrsponds to a positive chemical shift ΔHz .



Fig. S6. (**A**) S-H stretching mode (v(SH)) of thiol **1** in CCl₄ at different concentrations. At [**1**] = 0.06 M, solvent-thiol and thiol-thiol interaction are assumed to be minimal. (**B**) Effect of increasing amount of **DAA** on the v(SH) of thiol **1** initially dissolved in CCl₄ at 0.06 M.

Explanation about Fig. S5.

Another approach to study the solvation of a given thiol is the examination of the effects of increasing amount of solvent (or alkene) on its FTIR spectrum. Fig. 5A begins by showing the S-H stretching mode (v(SH)) of thiol 1 without solvent. For this neat thiol, the band is centred at 2569 cm⁻¹ and is quite broad because of H-bonding interactions where the sulfur atom acts as the H acceptor $(SH \bullet \bullet S)$.¹ Dilution with an apolar solvent such as CCl₄ causes a gradual narrowing of the S-H stretching band, as well as a marked shift to higher frequency (2583 cm⁻¹) indicative of minimal solvent-solute interactions. These observations are consistent with the progressive disruption of hydrogen-bonded complexes between thiol molecules. Below 0.06 M, the position and shape of the S-H stretching band no longer changes reflecting that most thiol molecules are thus in the monomeric (free molecules). Starting from this solution of 1 at 0.06 M in CCl_4 , Fig. 5B shows the effects of increasing amount of DAA on the S-H stretching mode. As more DAA is added, the originally sharp feature progressively broadens, moves to lower frequencies, and becomes more intense. This evolution is consistent with the formation of hydrogen bonds between the SH proton of **1** and the π electrons of C=C bonds of **DAA** acting as H acceptor, as already evidenced by NMR data.² Electron density transfer from olefin to the thiol causes a weakening of the S-H bond with a resultant red shift, elongation of the S-H bond and higher intensity in the SH stretching band. It should be noted that a similar trend is found when DAA is replaced by DVE and also DAP (Fig. S6). This supports the existence of analogous H-bonding interactions in other thiol-ene systems (SH•••C=C) with π electrons acting as H acceptor.

Experimental section - Thiol solvation by FTIR spectroscopy. For the analysis of neat thiols, **1** was sandwiched between two quartz plates using a 100 μ m Teflon O-ring. The FTIR spectrum was recorded at room temperature on a Bruker FTIR (IFS66/s) spectrometer in the 2000-4000 cm⁻¹ region with a DTGS detector. For the analysis of diluted solutions, 480 μ L of CCl₄ was placed in a 2-mm thick quartz cuvette (volume: 700 μ L, width 10 mm) closed by a septum stopper. Known volumes of the dithiol **1** were then injected (5 - 25 μ L) into the cuvette to vary the concentration (0.06 – 0.57 M). The FTIR spectra were recorded after each injection. To study the influence of the diene on the S-H stretching mode of **1**, a CCl₄ solution of thiol **1** of concentration 0.06 mM was placed in a 2-mm thick spectroscopic cuvette. Known volumes of the diene of interest were added to the cuvette to obtain a molar excess relative to the thiol varying between 6 and 30 times. The FTIR spectra were then recorded for each injection.

References. 1. J. G. David and H. E. Hallam, *Spectrochimica Acta*, 1965, **21**, 841–850. **2** . M. C. R. Symons and G. P. Archer, *J. Chem. Soc., Faraday Trans.* 1, 1988, **84**, 2499–2509.



Fig. S7. S-H stretching mode of thiol **1** in CCl_4 ([**1**] = 0.06 M) and in the presence of an increasing concentration of DVE (**A**), or DAP (**B**). Data were presented after a background subtraction of the spectrum from a corresponding diene solution in the absence dithiol **1**.



Fig. S8. The EPR spectra of the mixture 30 mM PBN, 100 mM thiol (**1** or **3**) in tert-butylbenzene with or without ITX (10 mM). The samples containing ITX were irradiated at 385 nm (2.7 mW cm⁻²) for 5 min to generate the thiyl radical via H-abstraction. The experiment involving ITX shows a similar but increased EPR signal compared to the system without sensitizer (ITX).



Fig. S9. Effect of thiol aging time on monomer (alkene) conversion for stoichiometric polymerization of bulk **DAA**-**1**. The experiment was performed under air and at ambient temperature **DAA** with dithiol **1**. Ref. corresponds to a freshly opened thiol bottle.



ΔH = 40.83 kcal mol-1

Fig. S10. Calculated reaction enthalpy $\Delta_r H$ (DFT calculation, method uB3LYP - Base 6-31G*) for MAH of thiol **1** by alkene **DAA**, **DAP** and **DVE**. It is found that the reaction enthalpy of a H-atom transfer of thiol **1** to alkene amounts to $\Delta_r H_{298} \approx 42$ kcal/mol and does not vary significantly with the nature of the alkene.

Table S1. Dependence of self-initiated polymerization rate of **DAA-1** (1:1 equiv) on impurities (relative to polymerization rate of a system without solvent). Dibutyl disulfide (TCI, > 98.5%), cumyl hydroperoxide (TCI, 80.5%), copper (II) sulfate pentahydrate (Carl Roth, >99%) were used as impurities.

Run	Concentration of impurity (M)	Relative R _p (h ⁻¹) ^a
Bulk DAA:1	-	1 ± 0.2
(Reference)		
+ Water	0.52	5.5 ± 0.2
+ Dibutyl disulfide	0.05	0.8 ± 0.2
+ Cumyl	0.10	1.1 ± 0.2
hydroperoxide		
+ Cu ²⁺	1.56 x 10 ⁻⁵	6.8 ± 0.2

^a Relative to the polymerization rate in bulk